

L Number	Hits	Search Text	DB	Time stamp
1	2482	(430/311).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 15:10
2	344	((430/311).CCLS.) and (( hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 15:17
3	106	((430/311).CCLS.) and (( hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)) and (Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 15:17
4	1473	(430/322).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 15:17
5	197	((430/322).CCLS.) and (( hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 15:17
6	77	((430/322).CCLS.) and (( hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)) and (Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 15:18
-	1	09/683929	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/22 16:52
-	6369	(430/5).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/22 16:52
-	69151	(( hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 15:11
-	1078592	(Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 15:11
-	18431	(( hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)) and (Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/22 17:57
-	7354	(( hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)) and (Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4))) and (mask or photomask or reticle) and (resist or photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/22 17:59

-	187	(((( hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)) and ( (Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4)))) and (mask or photomask or reticle) and (resist or photoresist)) and ((430/5).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/22 18:07
-	6	"6472107"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/22 18:08
-	23616	(Resist or photoresist) with (( hard or metal or etch\$3) adj (layer or film or mask))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 08:47
-	246	430/296.ccls. and ( (Resist or photoresist) with (( hard or metal or etch\$3) adj (layer or film or mask)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 10:13
-	166	(430/296.ccls. and ( (Resist or photoresist) with (( hard or metal or etch\$3) adj (layer or film or mask)))) and (Cr or chrom\$4 or W or tungsten or Ta or tantalum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 09:43
-	80	(430/296.ccls. and ( (Resist or photoresist) with (( hard or metal or etch\$3) adj (layer or film or mask)))) not ((430/296.ccls. and ( (Resist or photoresist) with (( hard or metal or etch\$3) adj (layer or film or mask)))) and (Cr or chrom\$4 or W or tungsten or Ta or tantalum))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 09:43
-	73	((430/296.ccls. and ( (Resist or photoresist) with (( hard or metal or etch\$3) adj (layer or film or mask)))) and (Cr or chrom\$4 or W or tungsten or Ta or tantalum)) and (charg\$4 or discharg\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/23 10:24